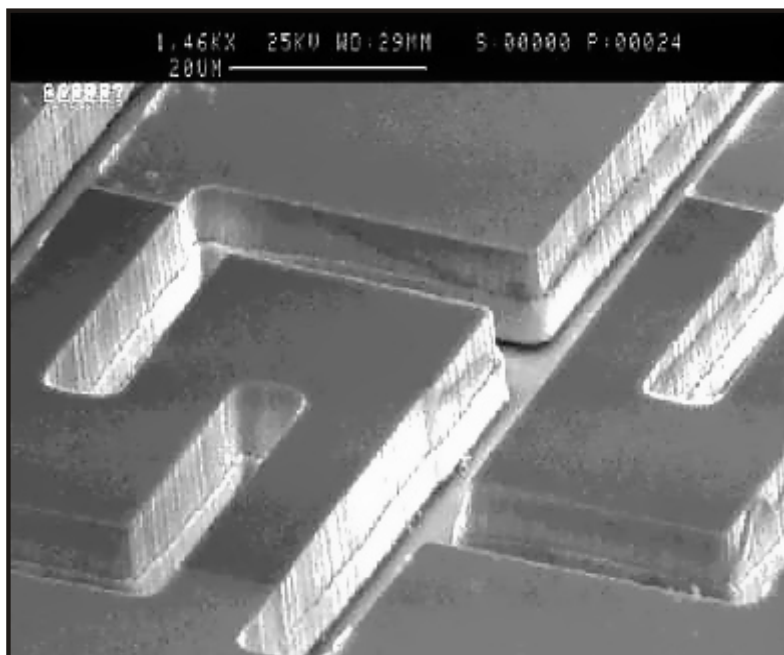
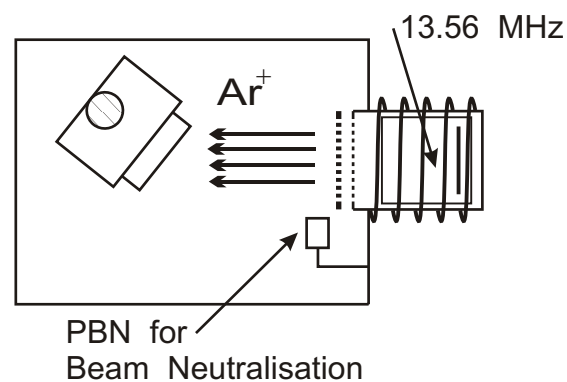


Ionfab Data

CMT - Ion Beam Etching



10 µm deep etch with excellent anisotropy
etched at the OPT application laboratory/ UK



Ion Beam Etching (Milling)



Ionfab 300 Plus

Technology:

- Ion Beam Etching
- He substrate cooling
- tiltable substrate holder
- substrate rotation
- RF source (filamentless)
- filamentless PBN

Results:

- Rate : 160 nm/ min
- Mask: Photoresist
- Uniformity: $\pm 5\%$